

Time evolution of beam intensity from ECRIS







Structure of the ECR ion sources (1970~2009)





Key words







ECR ion sources

: Brief History and Look into the next generation

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1. Physics of ECR plasma

Effect of key components on the ECR plasma and beam intensity

2. Technology of the ECR ion sources

Permanent magnet super-conducting magnet Example of most advanced ECR ion sources

3. Next generation

Super-conducting ECR ion source (>28GHz) New type ECRIS















Magnetic field configuration I (B_{min} effect)













Energy absorption as a function of B_{min}





Magnetic field configuration II (Mirror ratio)









Gas pressure effect







Scenario to increase the beam intensity







Frequency effect











q: charge state L: chamber length

> Chamber size (quadrumafios) 10times larger than caprice











Technology of the ECR ion source







Permanent magnet technology



All permanent magnet ECR ion source





All permanent magnet ECR ion source (LAPECRIS2)



Table 2 Typical performances of LAPECR2 in comparison with LECR2

Ion	LAPECR2 (eµA)			LECR2 (eµA)
O^{6+}	1000	1.0 kW	24 kV	610
O ⁷⁺	130	1.0 k W	24 kV	140
Ar ⁸⁺	460	0.9 kW	24 kV	460
Ar ⁹⁺	355	0.9 kW	24 kV	_
Ar^{11+}	166	1.08 kW	25 kV	185
Ar ¹²⁺	62	1.08 kW	25 kV	105
Ar^{14+}	16.7	1.05 kW	23 kV	12
Ar ¹⁶⁺	2	1.0 kW	25 kV	_
Ar ¹⁷⁺	0.33	1.08 kW	23 kV	_
Xe ²⁰⁺	85	1.0 kW	23 kV	_
Xe ²⁶⁺	40	1.05 kW	24 kV	50
Xe ²⁷⁺	24	1.05 kW	24 kV	25
Xe ³⁰⁺	5.3	1.05 kW	24 kV	_
Xe ³¹⁺	2	1.05 kW	24 kV	_









Heavy ion accelerator facility





Advanced ECR ion source I (VENUS)



B _{ini} /B _{ecr}	~ 4
B _{ext} /B _{ecr}	~ 2
B_{min}/B_{ecr}	~ 0.5 to 0.8
B _{rad} /B _{ecr}	≥ 2
B _{ext} / B _{rad}	\leq 0.9 to 1



		VENUS				
f(GHz)	28 or18 +28					
¹⁶ O	6	2850 ¹²⁹ X	e 28 ⁻	222		
	7^{-}	850	2 9 [°]	168		
⁴⁰ Ar	12	860	30-	116		
	14	514	31	86		
	16	270	34	41		
	17	36	37	12		
	18	1	38-	7		
			42 ⁻	.4		
²³⁸ U	33-	205				
	34	202				
	35-	175				
	47	5				
	50-	1.9				







Advanced ECR ion source II(SECRAL)







RIKEN 28GHz ECR ion source





Structure of SC-Coils





 I_c performance of the conductor with a rectangular shape and the load points for the solenoid SL1 and sextupole magnet.



The longitudinal distributions of the magnetic force acting on the straight region of the hexapole coils.











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2 GM-JT refrigerator is installed for Cooling the SC-Coils of RIKEN SC-ECRIS





Next generation (requirements)



New ECR ion source



Required beam intensity from ion source

 ${}^{6}\text{He}=2 \ 10^{13}$ atoms per second ${}^{18}\text{Ne}=8 \ 10^{11}$ atoms per second

High ionization efficiency

New 60GHz ECRIS





Next generation (Superconducting magnet technology)

36GHz ECRIS







Next generation (Heat load from X-ray)



$\sum_{C \in N} \frac{|A| | |K| | |K|$







Next generation (Plasma instability)

Beam from ECRIS







Next generation (New type ECRIS)

